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Docket No.: 055071-0310

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	:	Customer Number: 20277
Armin LIEBCHEN	:	Confirmation Number: 3610
Application No.: 10/705,234	:	Group Art Unit: 2851
Patent No.: 7,034,919 B2	:	
Filed: November 12, 2003	:	Examiner: Peter B. Kim
Issued: April 25, 2006	:	

For: METHOD AND APPARATUS FOR PROVIDING LENS ABERRATION
COMPENSATION BY ILLUMINATION SOURCE OPTIMIZATION

REQUEST FOR CERTIFICATE OF CORRECTION UNDER 37 CFR 1.322

Mail Stop CERTIFICATE OF CORRECTIONS
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Certificate
AUG 15 2006
of Correction

Sir:

In reviewing the above-identified patent, a printing error was discovered therein requiring correction in order to conform the Official Record in the application.

The error noted is set forth on the attached copy of form PTO-1050 Rev. 2-93 in the manner required by the Commissioner's Notice.

Specifically, on the title page, page 2, under OTHER PUBLICATIONS, in column 2, in the article by Nishrin Kachwala et al., the following phrase in the title should be corrected: ""160 run line" to - - **160 nm line** --. A copy of considered 1449, originally filed with the Information Disclosure Statement on August 8, 2005, showing the correct version of the title is attached for your information and convenience.

AUG 15 2006

10/705,234
7,034,919

The change requested herein occurred as a result of printing the Letters Patent and the Certificate should be issued without expense under Rule 322 of the Rules of Practice. Accordingly, Applicants request issuance of the Certificate of Correction.

Please charge any shortage in fees due in connection with the filing of this paper to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

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Date: August 11, 2006

**Please recognize our Customer No. 20277
as our correspondence address.**

WDC99 1269315-1.055071.0310

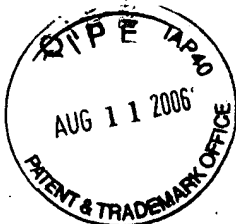
AUG 15 2006

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 7,034,919 B2
APPLICATION NO. : 10/705,234
DATED : April 25, 2006
INVENTOR(S) : Armin Liebchen

It is certified that an error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Title page, page 2, column 2, under "OTHER PUBLICATIONS",
In the article by "Nishrin Kachwala et al.", line 2, change "160 run line" to
-- 160 nm line --.



SHEET 2 OF 2

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
055071-0310SERIAL NO.
10/705,234APPLICANT
Armin LIEBCHENFILING DATE
November 12, 2003GROUP
2851

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
PK		US 5,880,588	10-21-1997	Gortych et al.	
		US 5,300,788	04-05-1994	Brunner et al.	
		US 5,805,290	09-08-1998	Ausschnitt et al.	
		US 5,965,309	10-12-1999	Ausschnitt et al.	
		US 5,680,588	10-21-1997	Gortych et al.	
		US 6,033,814	03-07-2000	Burdorf et al.	
		US 6,128,067	10-03-2000	Hashimoto	
		US			
		US			
		US			

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes - Number - Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
PK		JP 2000-232057A				X	

OTHER ART (including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
PK		BURN J. LIN, "The Exposure-Defocus Forest," Jpn. J. Appl. Phys. Vol. 33 (1994) pp 6758-6764
↓		M. DUSA et al., "Study of mask aerial images to predict CD proximity and line end shortening of resist patterns," Proc. of SPIE Vol. 4349 (2001), pp. 148-159
		B.P. MATHUR et al., "Quantitative Evaluation of Shape of Image on Photoresist of Square Apertures," IEEE Transactions of Electron Devices, Vol. 35, No. 3 (March 1988), pp. 284-297
↓		CHRISTOPHER J. PROGLER et al., "Merit functions for lithographic lens design," J. Vac. Sci. Technol. B 14(6), (Nov/Dec 1996), pp. 3714-3718
PK		NISHRIN KACHWALA et al., "Imaging contrast improvement for 160 nm line features using sub resolution assist features with binary, 6% ternary attenuated phase shift mask with process turned resist," SPIE Vol. 3679 (1999), pp. 55-67

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if references considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

AUG 15 2006